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Temporal Profile Measurements of Relativistic Electron Bunch Based on Wakefield Generation

International Beam Instrumentation Conference 2016

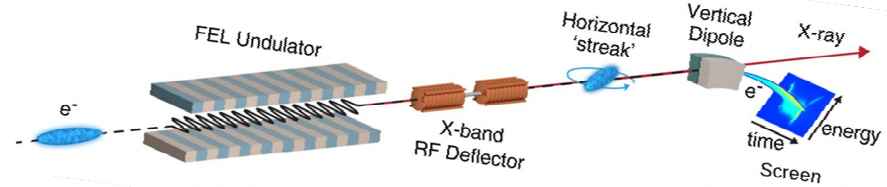
Barcelona, 13th September 2016

Talk outline

- ❑ **Longitudinal beam profile measurements using RF deflector**
- ❑ **SwissFEL and SwissFEL Injector Test Facility (SITF)**
- ❑ **Passive streaker model and wake potentials**
 - Formulas to calculate the beam longitudinal profile at the screen
 - Algorithm to time-resolve the electron beam profile
 - Example of reconstruction from numerical simulations
- ❑ **Proof-of-principle experiment at SITF**
 - Example of reconstruction from experimental data
- ❑ **Next steps at SwissFEL and at other labs**
- ❑ **Conclusions**

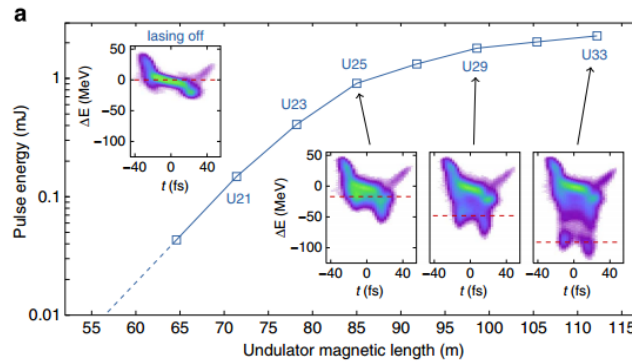
Longitudinal beam profile diagnostics

X-band transverse cavity very valuable instrument to:



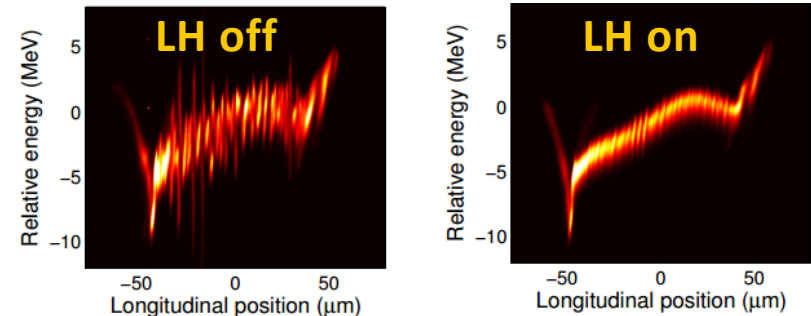
❑ Optimize the lasing along the bunch

[Ref. 1] C. Behrens et al.



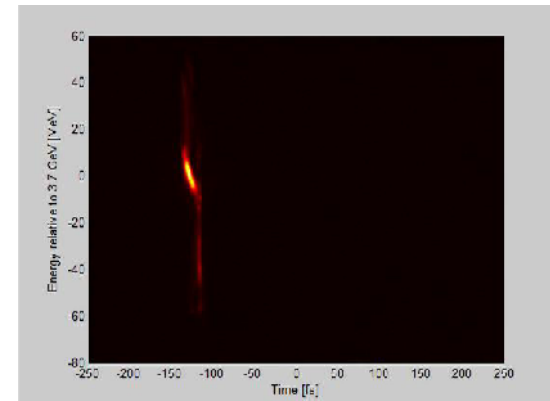
❑ Directly observe the microbunching instability and its mitigation

[Ref. 2] D. Ratner et al.



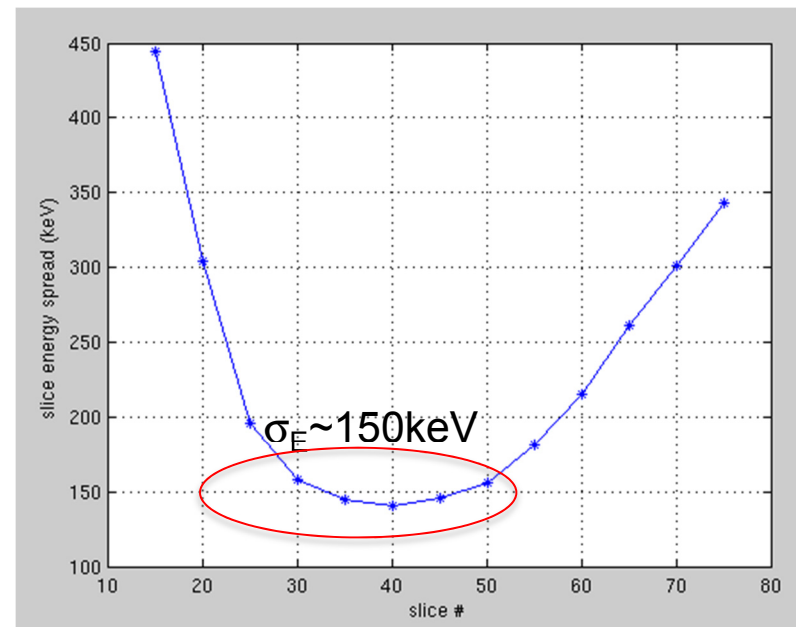
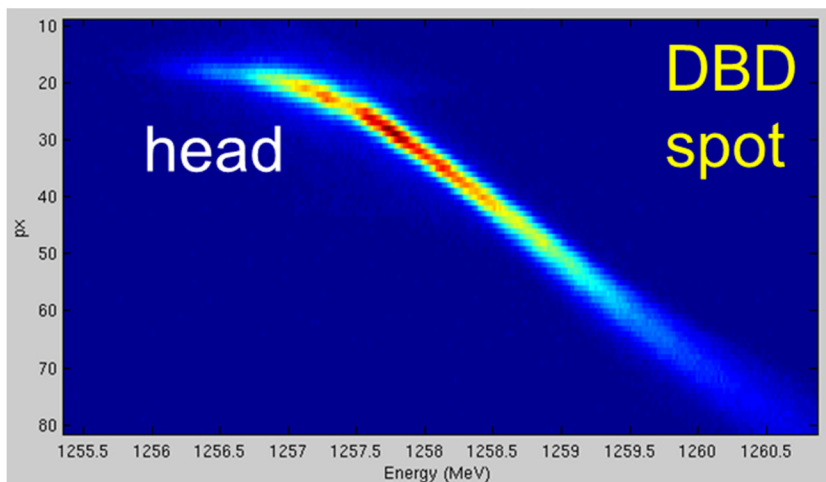
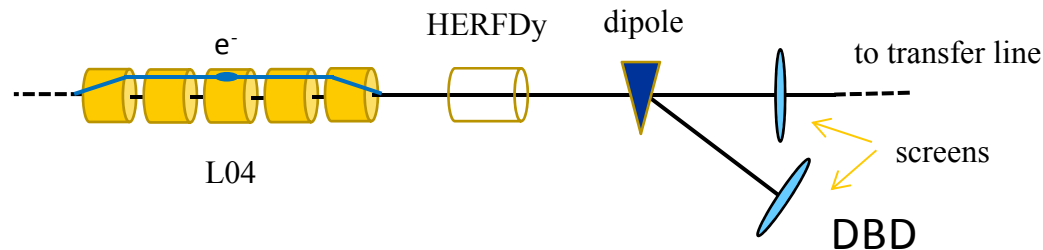
BUT:

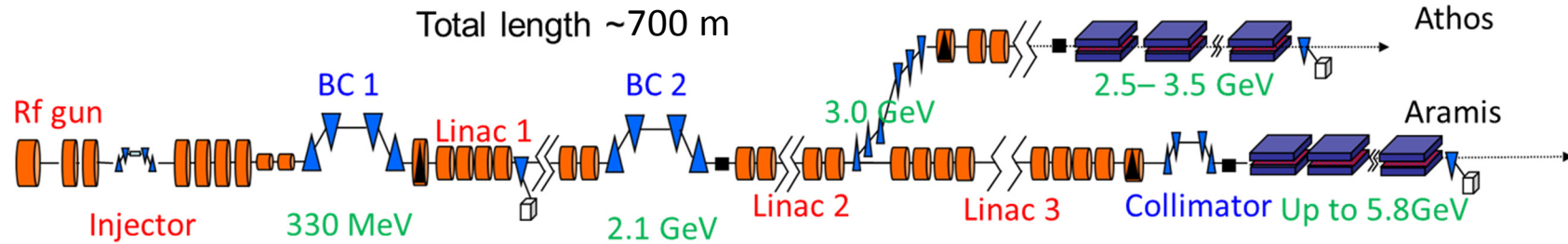
- ❑ Expensive manufacture
- ❑ Operation costs (powering, maintenance)
- ❑ It may suffer from jitter issues



First observation of passive streaking

- Slice Energy Spread at the FERMI@Trieste spectrometer with BC1+BC2 ($\sigma_t \approx 1\text{ps}$)
(...while waiting for High Energy RF Deflector at the end of 2011)
- Sending the beam off-axis in Linac 4 (high-impedance accelerating structures), used the transverse wakes to create a time-energy correlation





Electron source

RF gun with CaF_2 laser driven with Cs_2Te photocathode

Undulator beamlines

1. **Aramis:** hard X-ray FEL (1–7 Å). In-vacuum, planar undulators with variable gap, period = 15 mm
2. **Athos:** soft X-ray FEL (6.5–50 Å). Undulators with variable gap and full polarization control, period = 38 mm

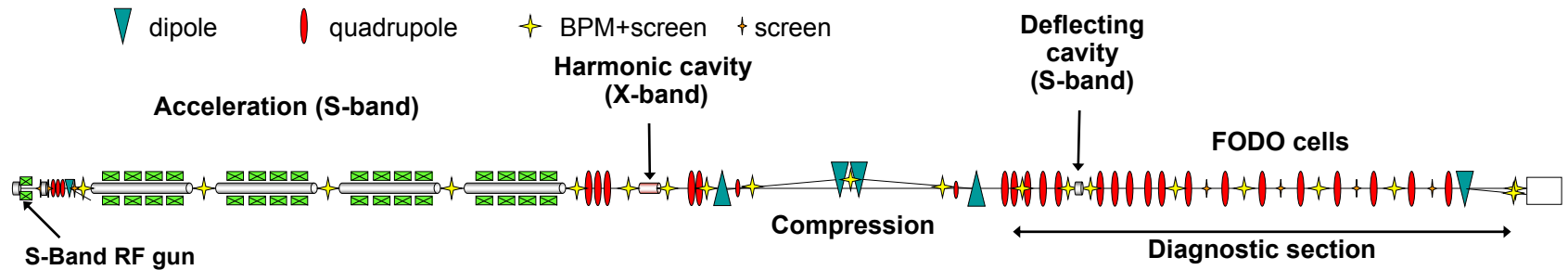
Wavelength	1 – 50 Å
Pulse duration	3 – 20 fs
Maximum e- beam energy	5.8 GeV
e- beam charge	10 – 200 pC
Repetition rate	100 Hz
Slice emittance (expected performances)	200 nm (10 pC) 300 nm (200 pC)
Slice energy spread	250–350 keV
Saturation length	< 50 m



- ☐ Construction started in 2013
- ☐ Commissioning started in Jul 2016
- ☐ Aramis user operation planned in Dec 2017
- ☐ Athos user operation planned in 2021

Missions

- ❑ Benchmark the simulation expectations and prove the feasibility of SwissFEL
- ❑ Develop and test components/systems and optimization procedures in SwissFEL



Commissioning phases

Phase 1: Electron source and diagnostics (2010)

Phase 2: Phase 1 + two S-band stations (2010-2011)

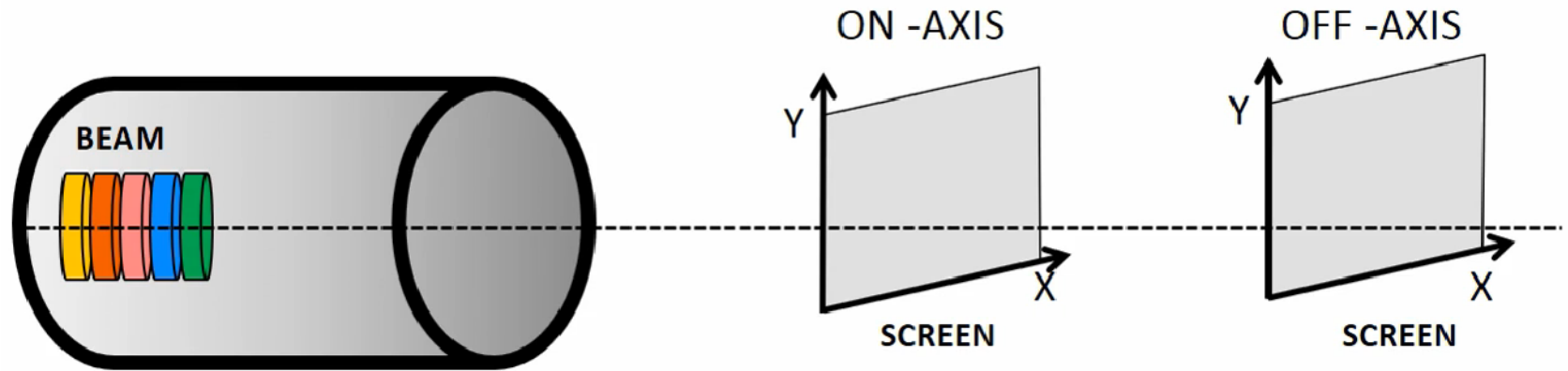
Phase 3: Machine in full configuration: all RF structures operational and bunch compressor installed (2012-2013)

Phase 4: Undulator installed for several weeks (2014)

Phase 4+: PSI gun installed (Oct 2014)

Shut-down: Oct 2014

Max e- beam charge	200 pC	
Laser longitudinal shape	Flat-top	Gaussian
Laser longitudinal length	9.9 ps FWHM	2.7 ps rms
Laser transverse shape	Cut Gaussian	
Laser transverse RMS	0.18 mm	
Max e- beam energy	266 MeV	
Repetition rate	10 Hz	



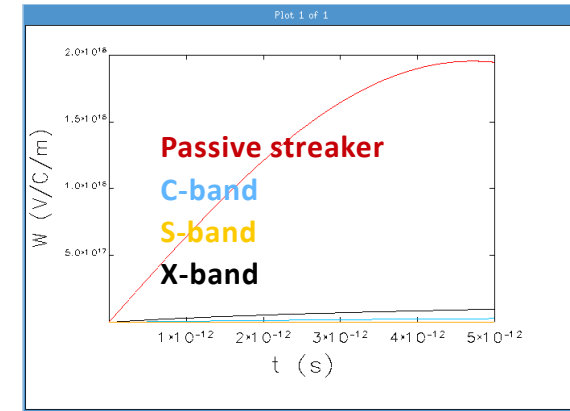
- ❑ The method to time-resolve the longitudinal profile is based on the self-transverse-wakefield generation
- ❑ A correlation between temporal position of the particle along the bunch and transverse position at a downstream screen is introduced
- ❑ The beam passes off-axis through a structure capable of generating a strong monotonic transverse wakefield along the full bunch length
- ❑ Cylindrical or planar, corrugated or dielectric-lined geometries may be used without altering the principle
- ❑ Potentially $\sim$ fs resolutions achievable

Suitable wakefield sources

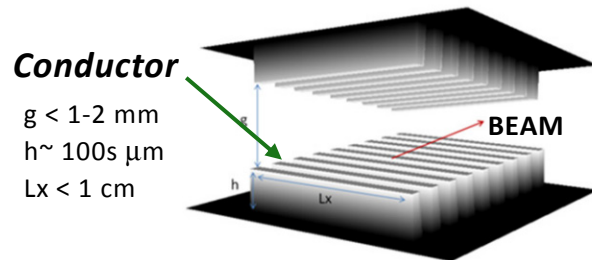
- Several sources can be used to do such a measurements.

The requirements are:

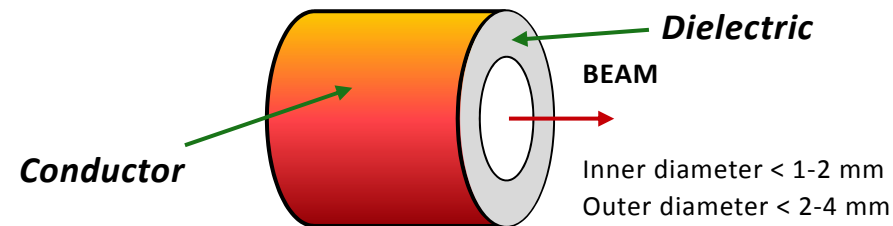
- Function monotone along the full bunch length
- Amplitude of the wakefield enough to limit the length of the device to a reasonable value (~few meters)



CORRUGATED



DIELECTRIC LINED-WAVEGUIDE



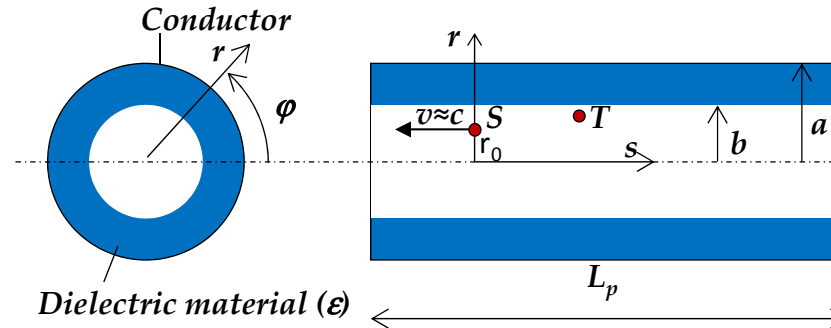
More typically
corrugated



Flat	Round
Easily tunable	More difficult to tune
Reduced amplitude (by $\pi^2/16$)	Maximum amplitude
	Possible charging effect



More typically
dielectric lined



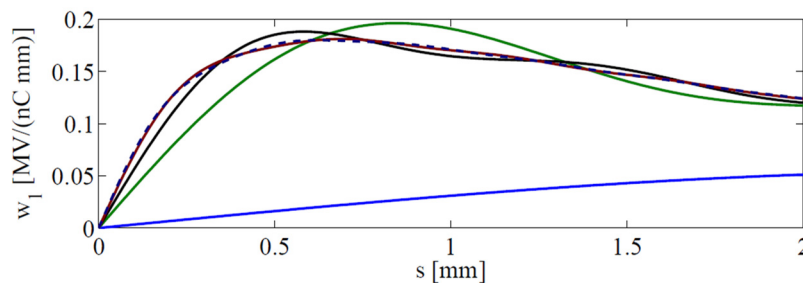
- Wakefield point charge is a linear combination of several sinusoidal functions:

$$w_{r,m}(s, r, r_0, \varphi, \varphi_0) = \frac{Z_0 c}{4\pi a^2} \left(\frac{r}{a}\right)^{m-1} \left(\frac{r_0}{a}\right)^m \sum_{i=1}^{\infty} A_{m,i} \sin(k_{m,i}s) \cos[m(\varphi - \varphi_0)]$$

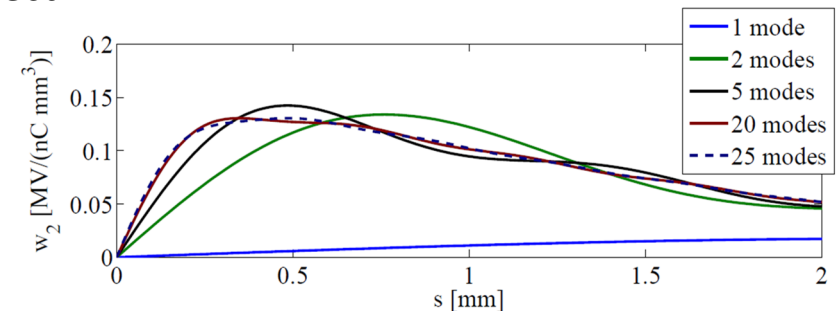
[Ref. 3] K. Y. Ng

$$w_{\varphi,m}(s, r, r_0, \varphi, \varphi_0) = \frac{Z_0 c}{4\pi a^2} \left(\frac{r}{a}\right)^{m-1} \left(\frac{r_0}{a}\right)^m \sum_{i=1}^{\infty} A_{m,i} \sin(k_{m,i}s) \sin[m(\varphi - \varphi_0)]$$

- The different modes build up increasing the effect



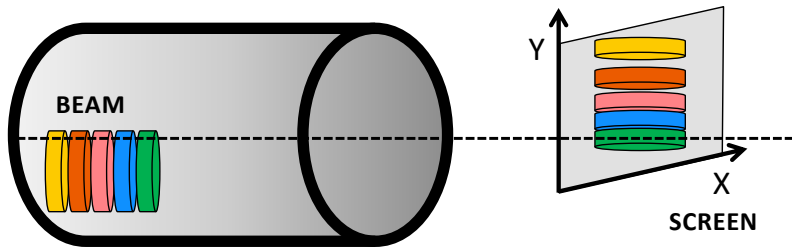
Dipole wake function (m=1)



Quadrupole wake function (m=2)

- Transient effect at the entrance of the tube neglected
- Wake functions were also verified with ImpedanceWake2D code

From the passive streaker to the screen



- ρ_L Longitudinal charge distribution at the streaker
- ρ_y Vertical charge distribution at the screen
- $\rho_{T,y}$ Vertical charge distribution at the screen (finite size)
- $\tilde{\rho}_{0,y}$ Vertical charge distribution at the screen (passing on-axis through the passive streaker)

From the charge conservation:

$$\rho_y dy = \rho_L ds \quad \Rightarrow \quad \rho_y = \rho_L \frac{ds}{dy} \equiv \rho_L s'$$

Transverse displacement at the screen location

$$y_s(s) \approx \frac{QL_p R_{34}}{E} [W_{r,1}(r_0, s) + W_{r,2}(r, r_0, s)]$$

Dipole wake potential: $W_{r,1} \propto r_0$

Quadrupole wake potential: $W_{r,2} \propto r_0^2, r$

Wake potentials when the transverse size is much smaller than the offset along the streaker:

$$W_{r,m}(r, s; r_0) = \int_{-\infty}^s w_r(r, r_0, s') \rho_l(r_0, s - s') ds$$

Finite beam size

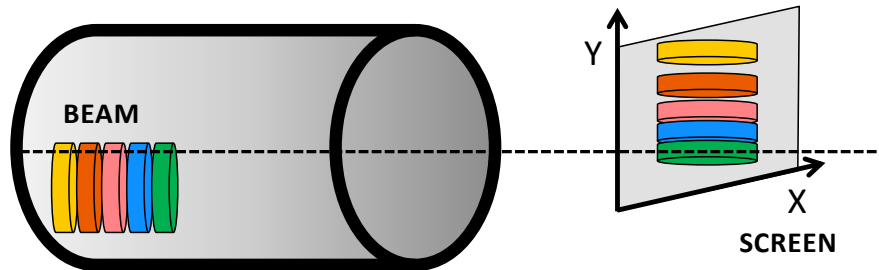
- ☐ The beam size is not negligible
- ☐ The profile at the screen, $\rho_{T,s}$, is evaluated as:

$$\rho_{T,y} = \rho_y \otimes \tilde{\rho}_{0,y}$$

Assumptions

- ☐ The transverse beam parameters are independent of the longitudinal coordinate
- ☐ The optics between the tube and the screen is linear

Time-resolving algorithm

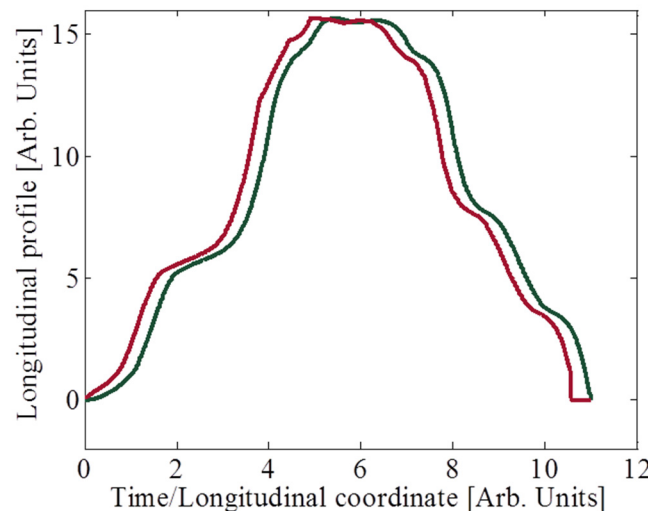


- ρ_L Charge distribution at the streaker
- ρ_y Transverse charge distribution at the screen (off-axis in the streaker) from ρ_L
- $\tilde{\rho}_L$ Trial charge distribution at the streaker
- $\tilde{\rho}_y$ Calculated transverse charge distribution at the screen (off-axis in the streaker) from $\tilde{\rho}_L$

The algorithm minimizes the cost function (neglecting the finite transverse beam size at the passive streaker):

$$\text{cost function} = |\rho_y - \tilde{\rho}_y|$$

changing ρ_L , modeled as a piecewise cubic polynomial

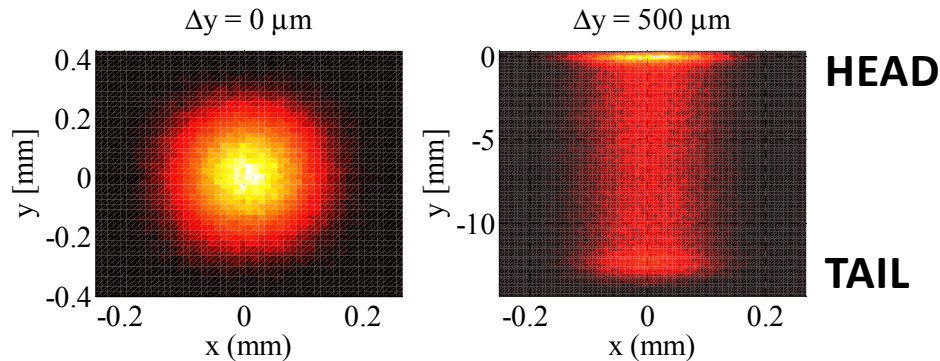


ρ_y assumed

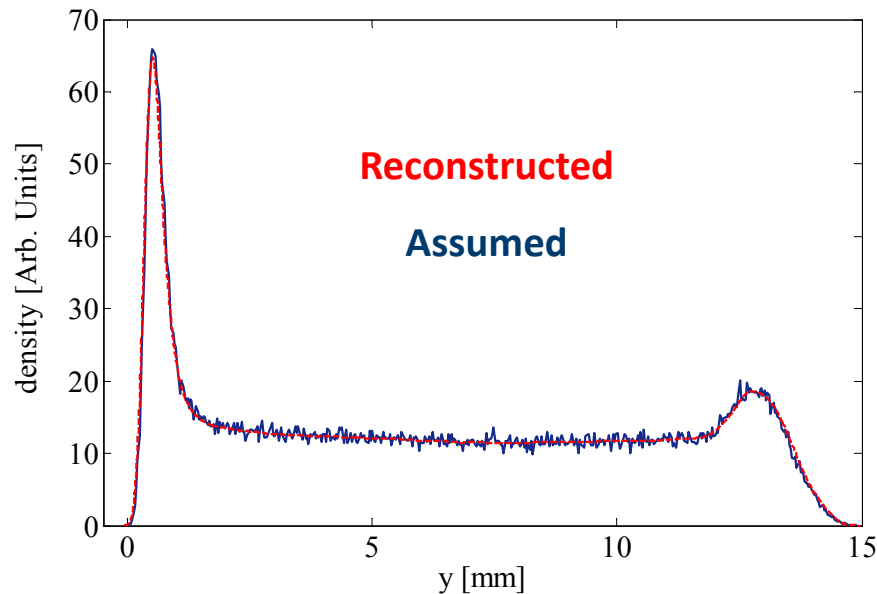
ρ_y reconstructed

Including the beam transverse size $\rho_{T,s}$ is used in the optimization

- Simulated in Elegant [Ref. 4] a wakefield source monotonic along the full bunch length
- Double horned current profile (LCLS undulator like)



- Only the dipole included
- Beam at the head poorly streaked
- Transverse size is a small fraction of the streaked image

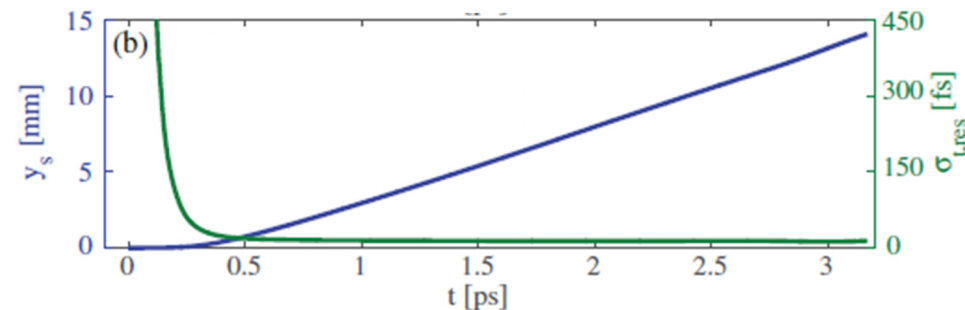


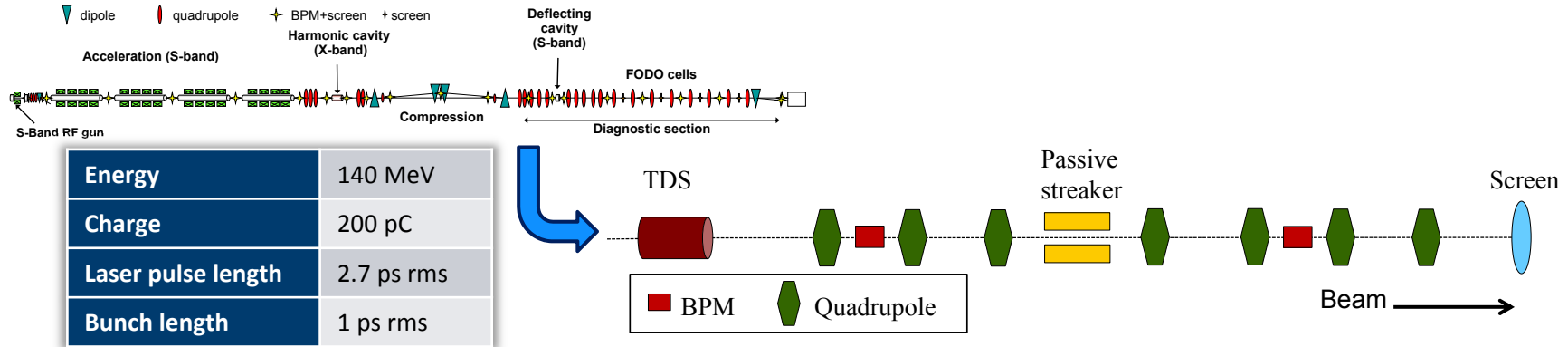
Calibration factor:

$$S = \frac{dy_s}{ds}$$

Resolution:

$$\sigma_{s,res} = \frac{\tilde{\rho}_{0,scr}}{S}$$

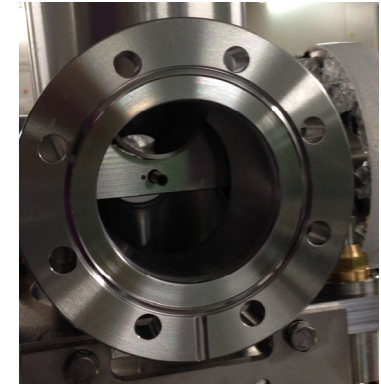




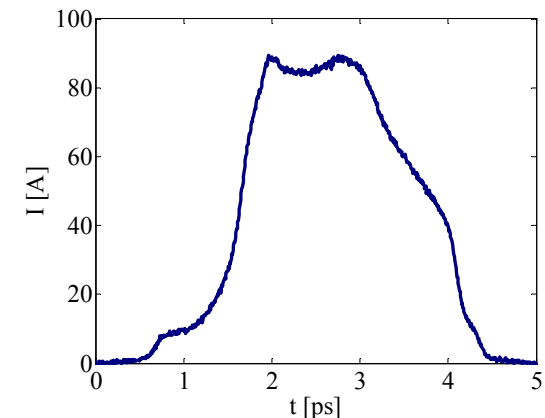
Material	Alumina
Dielectric constant	10
Metallization	~20 um
Internal diameter	1.65 mm
External diameter	2.40 mm
Length	9.5 cm



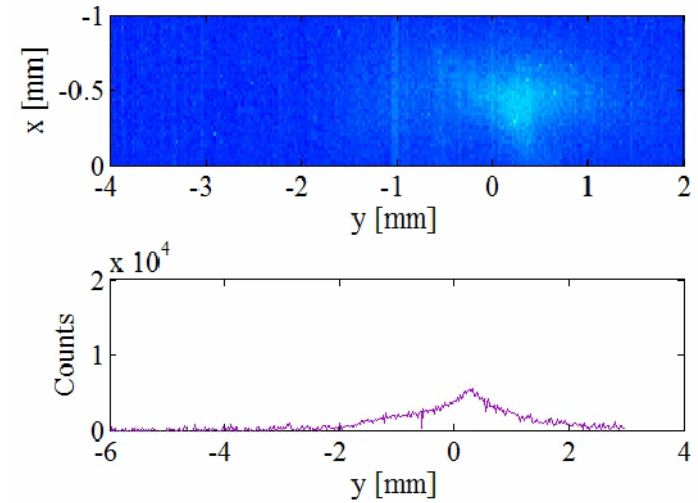
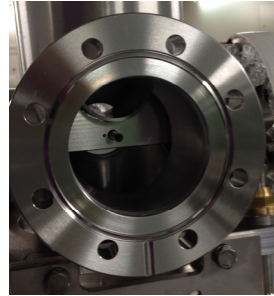
- ❑ Streaker mounted on a vertical remotely movable support
- ❑ Metallization with Cu layer



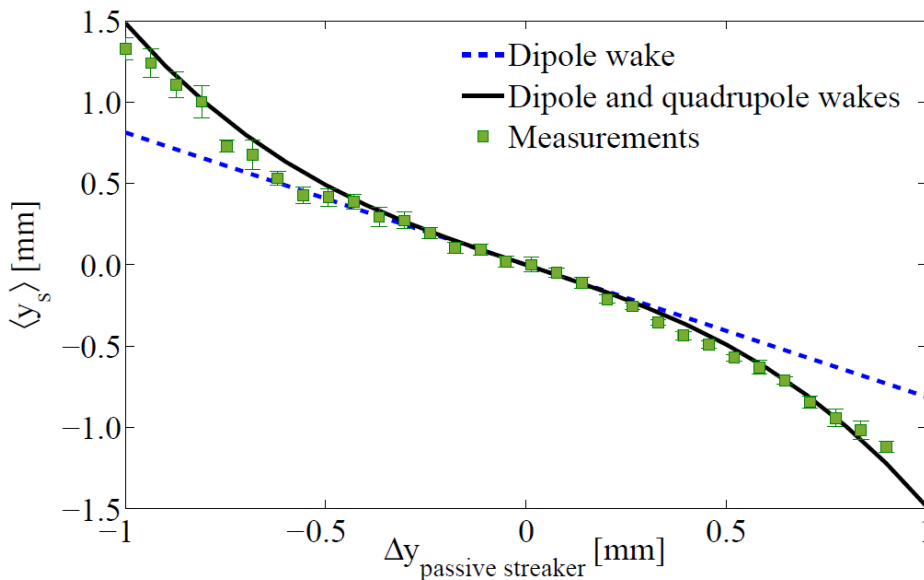
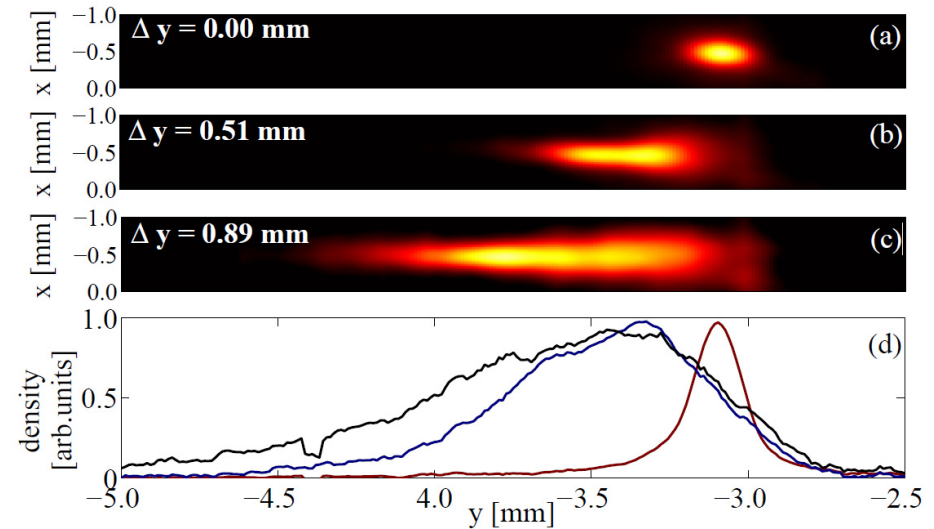
- ❑ Beam compressed to have a length compatible with a monotonic wakefield point charge
- ❑ Limited space for the streaker ($L_p = 9.5$ cm)
- ❑ Lowered the beam energy to enhance the effect ($y_s(s) \propto \frac{1}{E}$)
- ❑ Phase advance in the vertical plane between the streaker and the screen to maximize the resolution



- ❑ Shifted the position of the tube
- ❑ Measured the centroid of the beam on a downstream screen
- ❑ Centroid kick calculated



- ❑ Shifted the position of the tube
- ❑ Measured the centroid of the beam on a downstream screen
- ❑ Centroid kick calculated



- ❑ The kick factor can be expressed as:

$$K = C_1 \Delta y + C_3 \Delta y^3$$

	Model	Measured
C_1 [MV/(nC·m·mm)]	0.62	0.63
C_3 [MV/(nC·m·mm ³)]	0.52	0.43

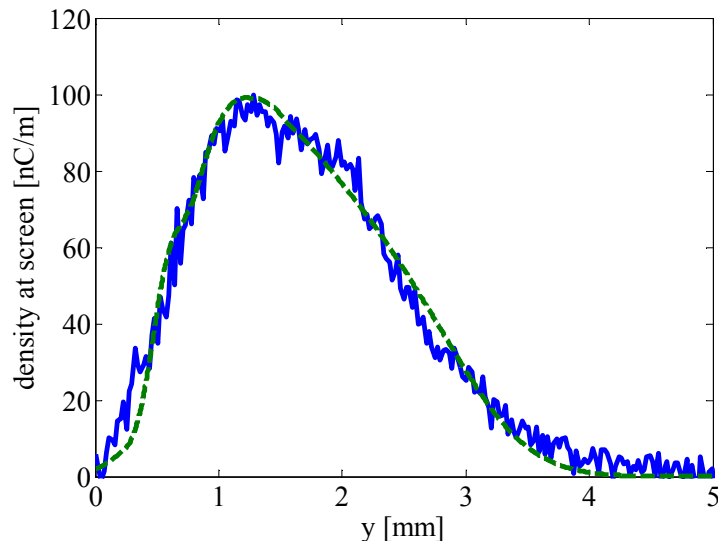
- ❑ Quadrupole effect not negligible for $\Delta y > 0.3$ mm

Defocusing due to the quadrupole

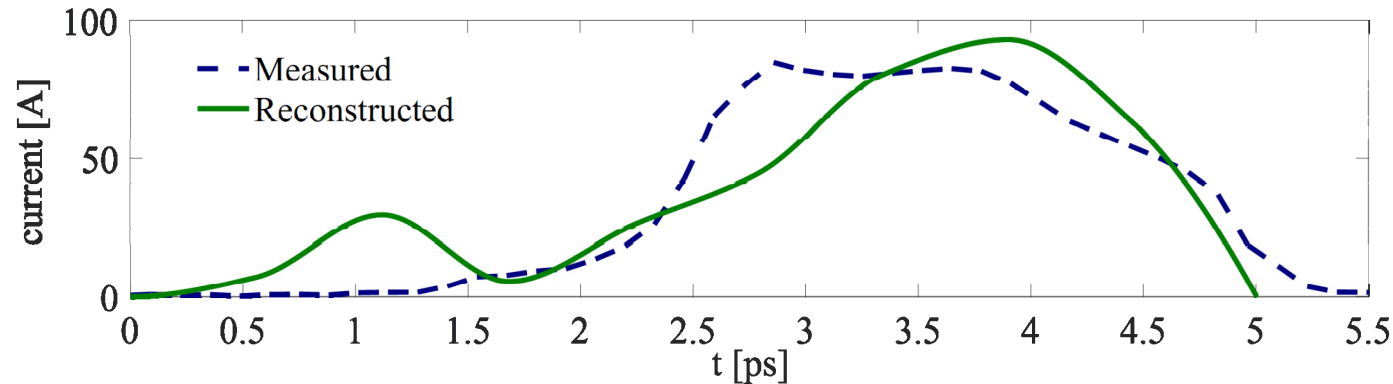
- More important if the beam size is large compared to the aperture of the device or the beam is more off-centered
- The charge distribution at the screen used for the convolution, to include the defocusing effects for a transverse beam distribution at the streaker is given by the expression:

$$\rho_{\text{screen}}(y_s) = \int \rho_{\text{screen}}(\tilde{y}_s) \rho_{\tau} \left[\frac{\Delta y (y_s - \tilde{y}_s)}{y_{sq}(\tilde{y}_s)} \right] \frac{\Delta y}{y_{sq}(\tilde{y}_s)} d\tilde{y}_s$$

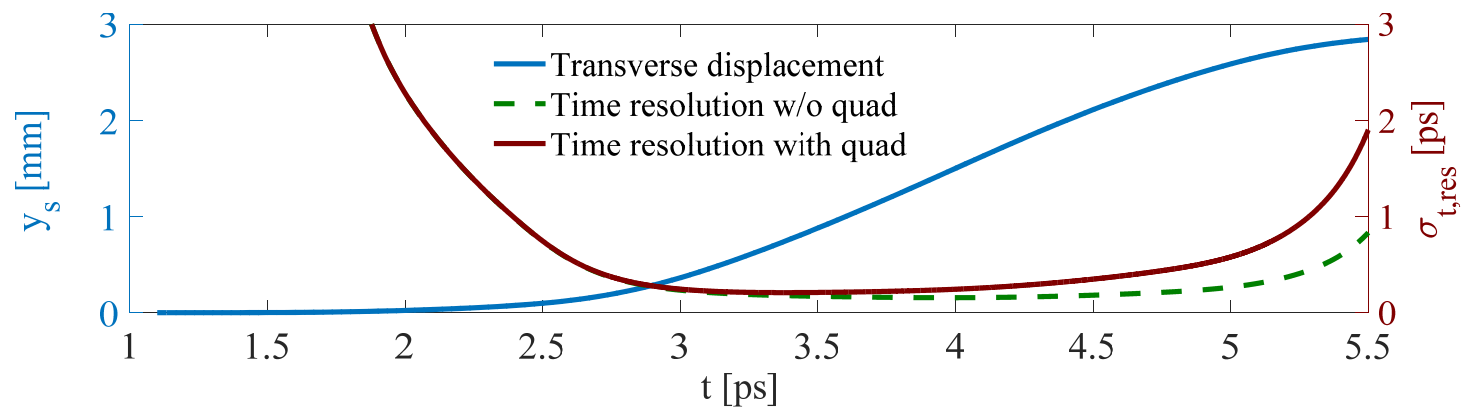
- y_{sq} is the transverse displacement of the beam at the screen due to the quadrupole wake only, for a particle at offset Δy at the passive streaker, and that is deflected to the coordinate y_s at the screen



- Green: convolution with dipole and quadrupole wake functions, defocusing effect due to quad and finite emittance
- Blue: measured transverse profile at the screen

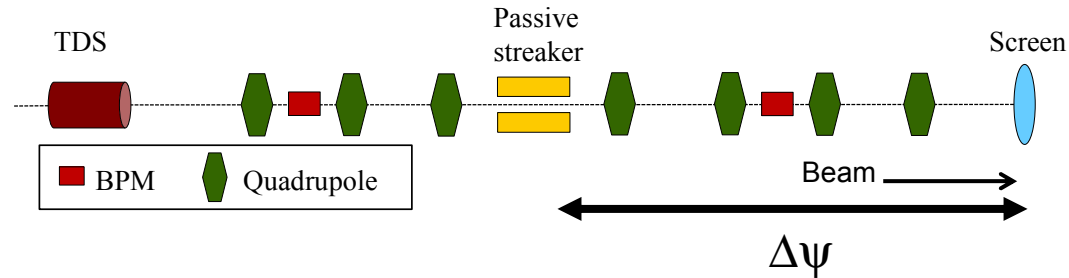


- The method demonstrated to be able to reconstruct the FWHM of the beam experimentally with a limited 9.5 cm length device (space limitations at SITF)

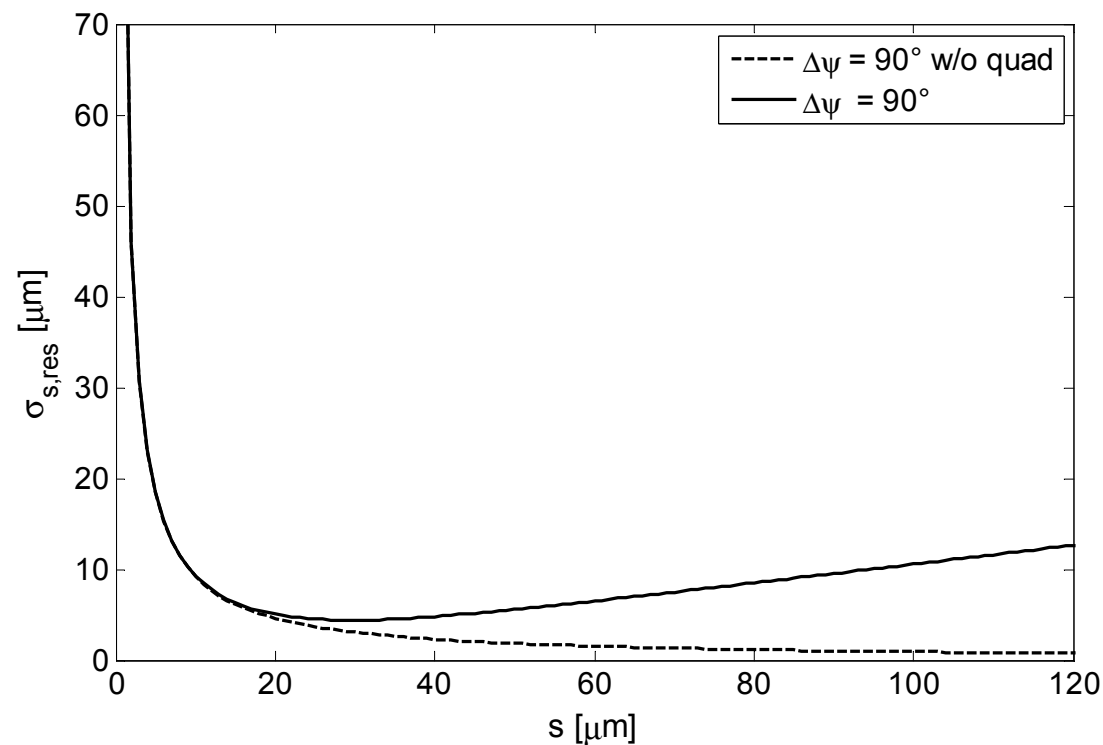


- The resolution of the method is determined by the wakefield source, and the beam size along the streaker:
 - is poor at the head of the beam (no streaking)
 - depends on the quadrupole effect going from the head towards the tail

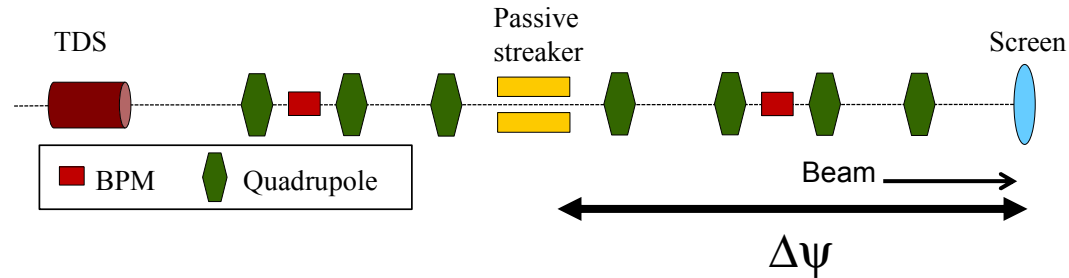
Resolution optimization



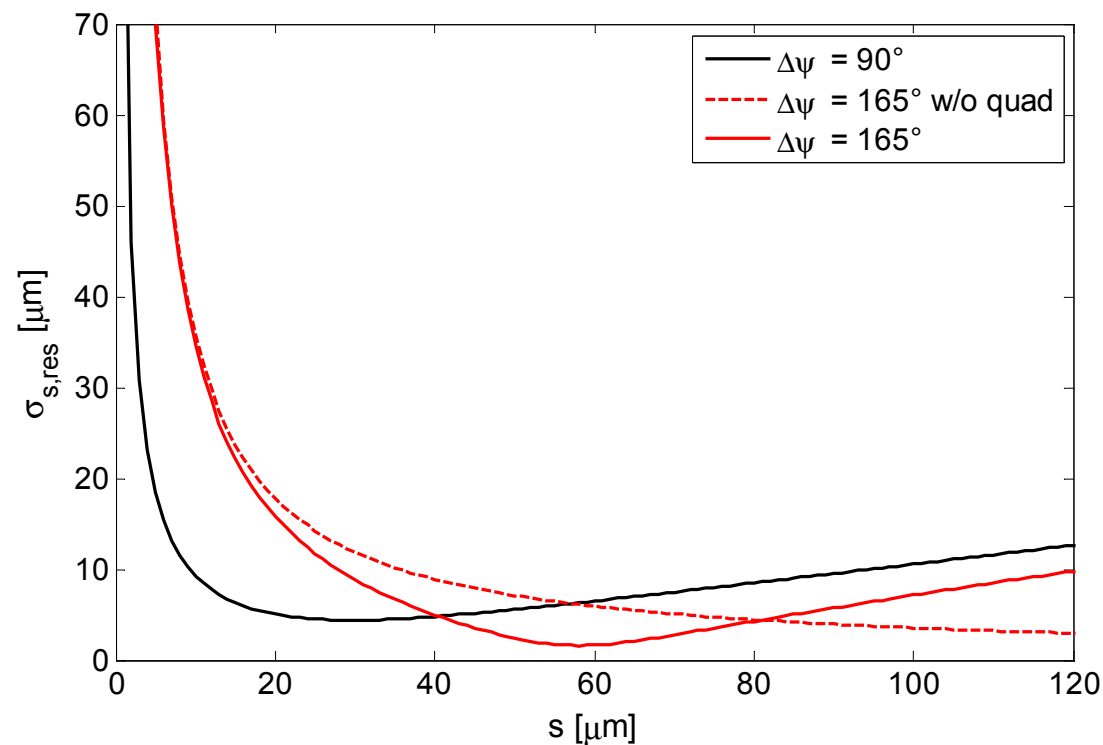
Scan of the phase advance between the passive streaker and the profile monitor may be an efficient way to optimize the resolution of the measurement



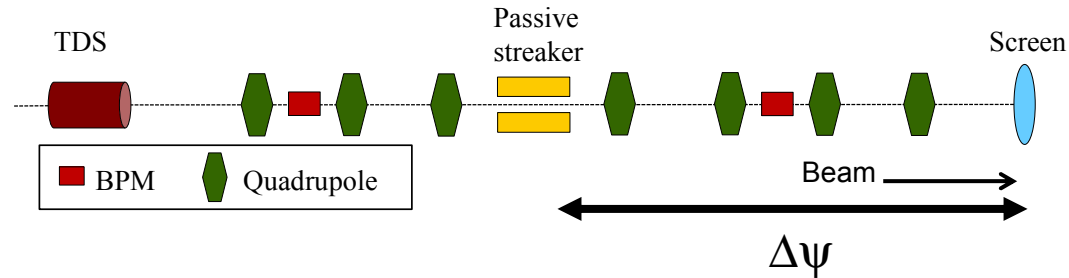
Resolution optimization



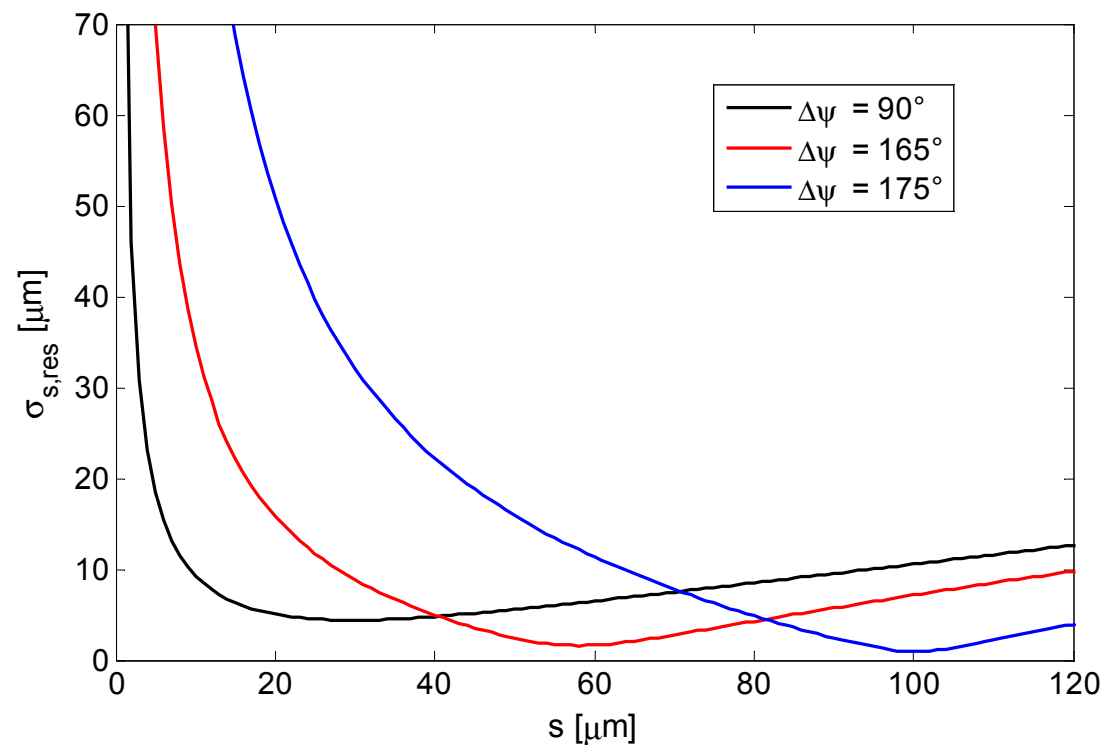
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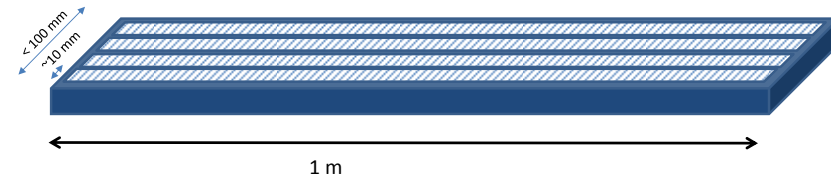
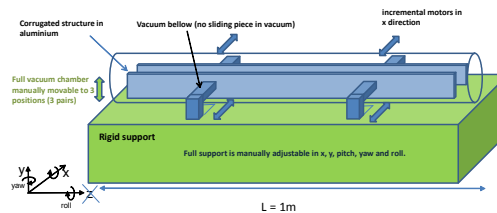
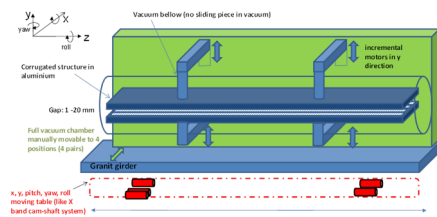
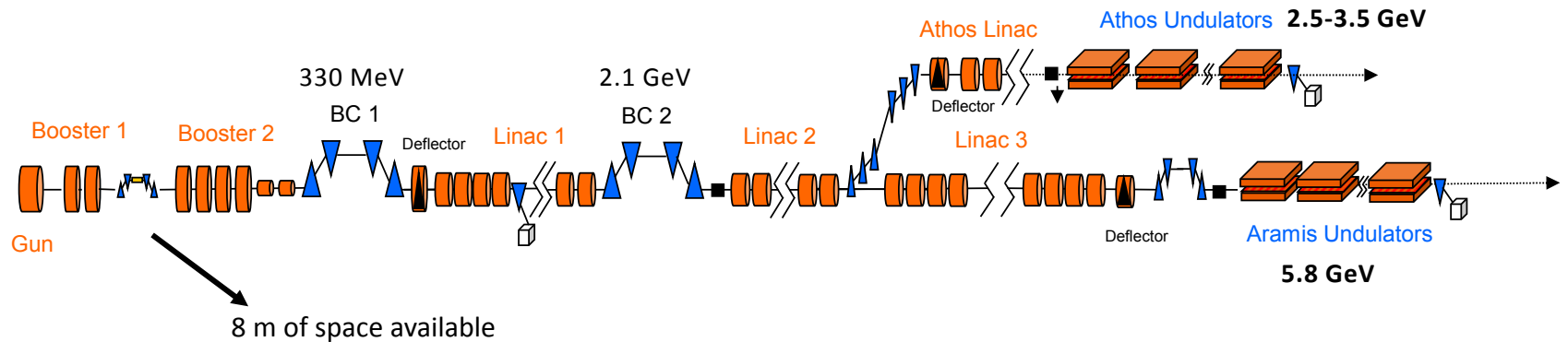


Resolution optimization



Scan of the phase advance between the passive streaker and the profile monitor may be an efficient way to optimize the resolution of the measurement





Installation of two passive structures 1 m length each upstream of BC1 to:

- ❑ Measure the wakefield in view of the dechirper installation for Athos: $\lambda \sim 2$ mm
- ❑ Alternatively linearize (following idea in [Ref. 6]): $\lambda \sim 6$ mm
- ❑ Test the two-color generation via wakefield excitation [Ref. 7]: $\lambda \sim 1$ mm

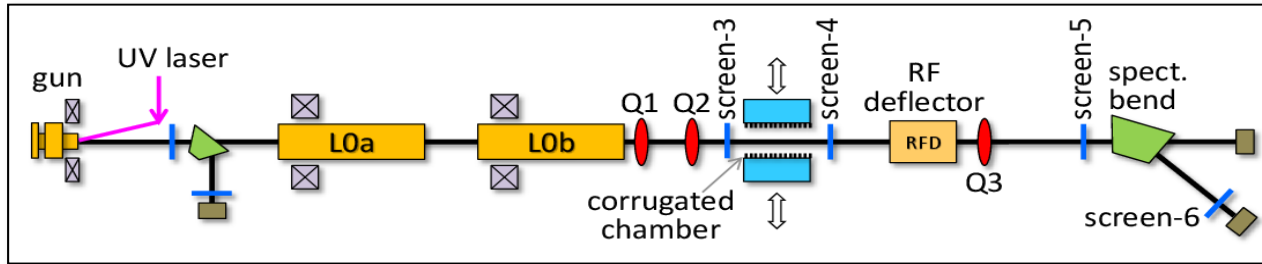


- ❑ Continue the streaking and reconstruction experience with a longer length device
- ❑ Corrugated surface, but equivalent to the dielectric line waveguide in terms of beam dynamics

Passive streaking at PAL

A longitudinal phase space measurement by corrugated structure

[Ref. 8] J. Hong, C. H. Kim, H.-S. Kang



e^- beam:

$E = 85 \text{ MeV}$

$\sigma_z = 0.45 \text{ mm}$

$Q = 200 \text{ pC}$

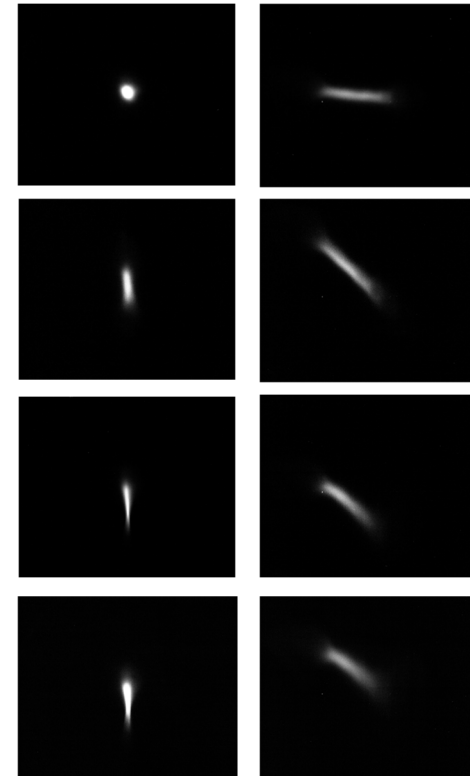
Dechirper gap 28 mm (OUT), deflector OFF

Dechirper OUT, deflector ON

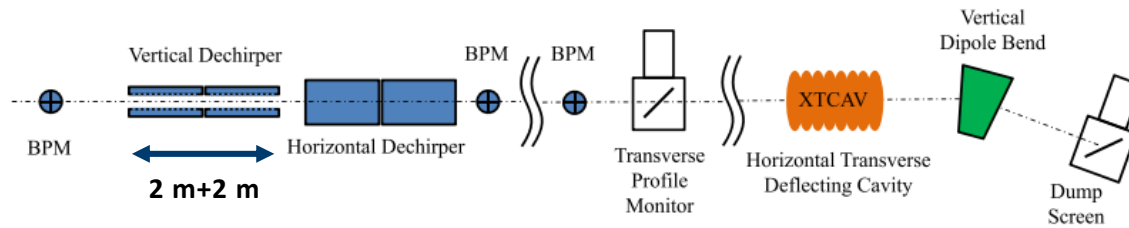
Dechirper gap 8 mm, offset 2 mm, deflector OFF

Dechirper gap 6 mm, offset 1 mm, deflector OFF

screen-5 screen-6

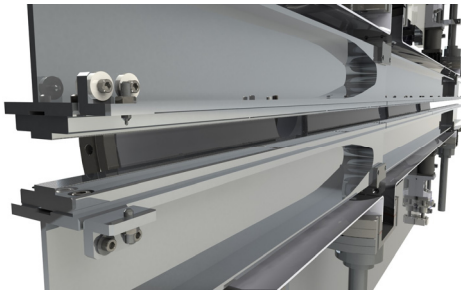


Passive streaking at LCLS



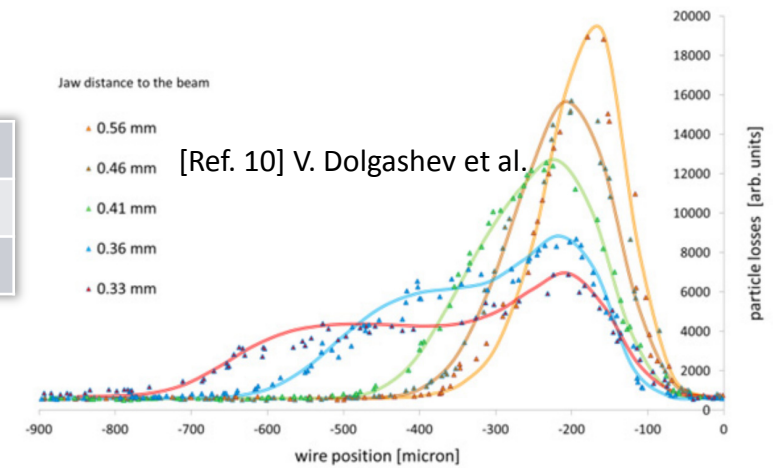
Measurement

LCLS Dechirper by RadiaBeam System



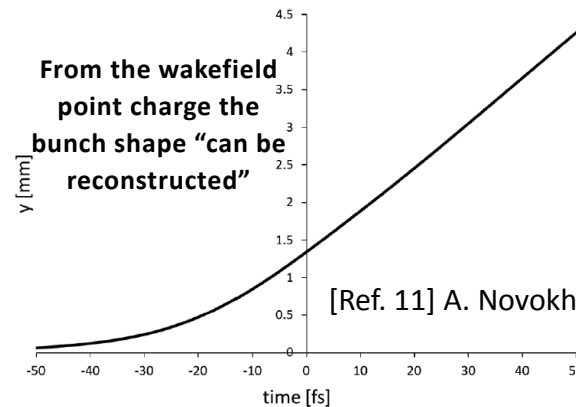
[Ref. 9] K. Bane, G. Stupakov

E	13.3 GeV
σ_t	50 fs (FWHM)
Q	185 pC



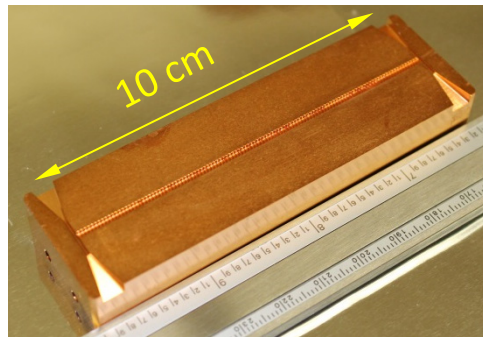
Simulation

E	4 GeV
σ_t	10 fs (rms)
Q	100 pC
Gap	3 mm
offset	1 mm

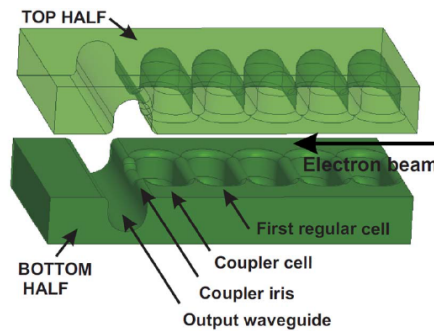


$$\sigma_{t,res}(s) \approx 1fs$$

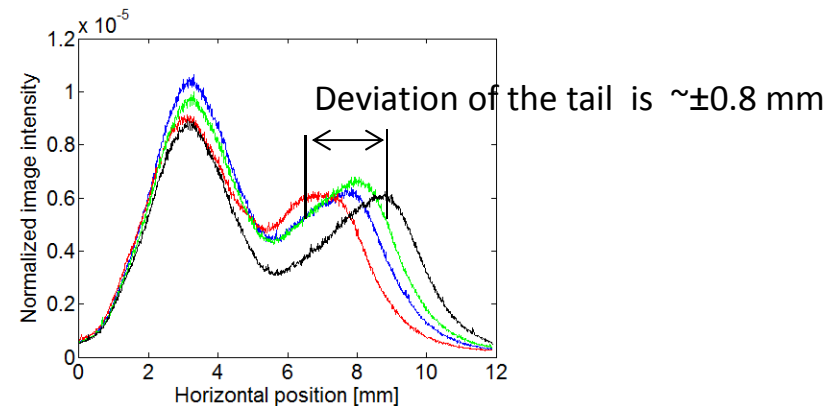
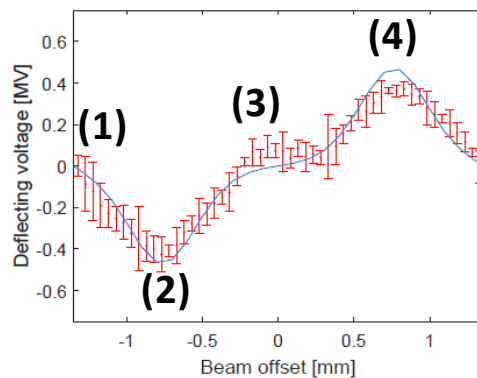
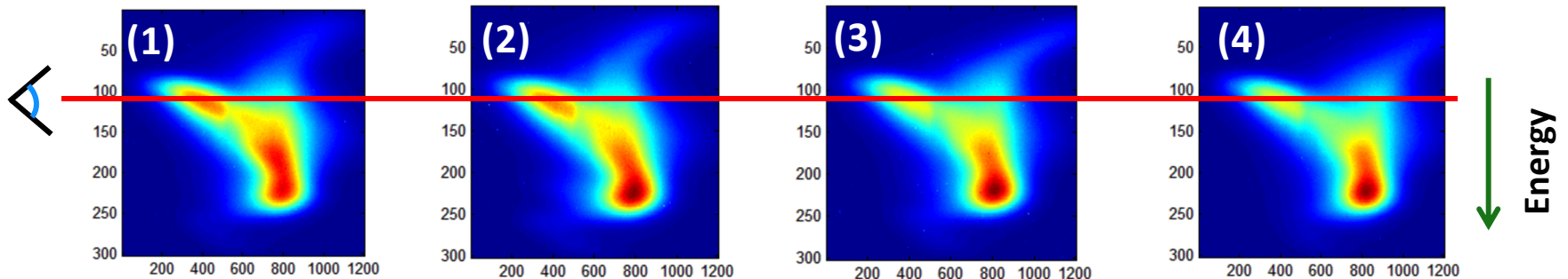
Accelerating structure at 100 GHz



[Ref. 12] M. Dal Forno et al.

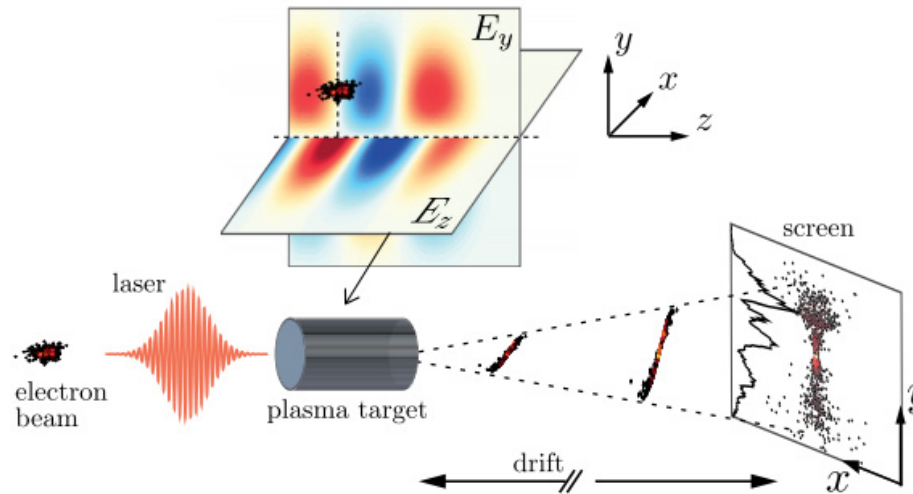
**Beam parameters at FACET**

- beam energy $E = 20.35$ GeV
- bunch charge $q = 3.2$ nC
- bunch length $\sigma_z = 50$ μm



A short-pulse laser drives a linear wakefield in a plasma target. The electron bunch is situated off-axis at the transverse maximum and longitudinal zero-crossing of the transverse fields

[Ref. 13] I. Dornmair et al.



Q	0.5 pC
σ_z	7.5 fs (rms)
E	110 MeV
σ_{TRANSV}	17 μm



- ❑ Simulated resolution ~ 0.1 fs in the core of the beam
- ❑ Second order dependence of the electric field on the transverse coordinate degrade the resolution at the head and tail

- ❑ Plasma generation complex
- ❑ High power laser
- ❑ Synchronization with the beam



- ❑ A *passive streaker* based on the self-transverse-wakefield can be used to effectively streak the electron beam
- ❑ An algorithm to reconstruct the electron bunch longitudinal profile has been proposed and verified with simulations
- ❑ A proof-of-principle experiment was performed at SITF
- ❑ Passive streaking presents pros and cons compared to a standard RF deflectors:

Pros:

- ✓ Single shot measurement
- ✓ Self-synchronized with the beam
- ✓ Cheaper to manufacture and operated (passive) compared to other existing devices
- ✓ Potentially fs or sub-fs resolutions achievable

Cons:

- Necessary to know beam energy, charge and optics
- Temporal resolution is not constant along the beam
- If relation between beam at the device and beam at the screen is non-linear, inversion requires more complicated computation

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